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Tantalum/ Nitrogen and n-type WO₃ Semiconductor/FTO Structures as a Cathode for the Future of Nano Devices

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Retraction Note:

The article entitled “Tantalum/ Nitrogen and n-type WO₃ Semiconductor/FTO Structures as a Cathode for the Future of Nano Devices,” has been accepted for publication in the Archives of Applied Science Research considering the statements provided in the article as personal opinion of the author which was found not having any conflict or biasness towards anything. As the article was a perspective one, information provided by the author was considered as an opinion to be expressed through publication.

Publisher took decision to make the article online solely based on the reviewers suggestion which considered the article not but a personal opinion of the author. However, it is found that the author have some personal concerns and issues, therefore, being retracted from the journal.

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